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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

2823

Applicant: Fernando Gonzalez et al.

Title: METHOD TO CHEMICALLY REMOVE METAL IMPURITIES FROM POLYCIDE GATE
SIDEWALLS

Docket No.: 303.775US1

Filed: August 30, 2001

Examiner: George Fourson

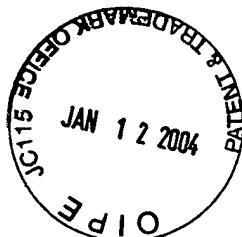
Customer No.: 21186

Serial No.: 09/945553

Due Date: January 9, 2004

Group Art Unit: 2823

Confirmation No.: 1842



MS Non-Fee Amendment

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

We are transmitting herewith the following attached items (as indicated with an "X"):

A return postcard.
 A Response to Restriction Requirement and Preliminary Amendment(13 Pages).

If not provided for in a separate paper filed herewith, Please consider this a PETITION FOR EXTENSION OF TIME for sufficient number of months to enter these papers and please charge any additional fees or credit overpayment to Deposit Account No. 19-0743.

SCHWEGMAN, LUNDBERG, WOESSNER & KLUTH, P.A.

Customer Number 21186

By: Suneel Arora
Atty: Suneel Arora
Reg. No. 42,267

CERTIFICATE UNDER 37 CFR 1.8: The undersigned hereby certifies that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail, in an envelope addressed to: MS Non-Fee Amendment, Commissioner for Patents, P.O.Box 1450, Alexandria, VA 22313-1450, on this 9 day of January, 2004.

Name

Tina Kohaut

Signature

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SCHWEGMAN, LUNDBERG, WOESSNER & KLUTH, P.A.

Customer Number 21186
(GENERAL)



PATENT

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Applicant: Fernando Gonzalez et al. Examiner: George Fourson
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POLYCIDE GATE SIDEWALLS

RESPONSE TO RESTRICTION REQUIREMENT
AND PRELIMINARY AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

In response to the Restriction Requirement mailed December 9, 2003, please amend the application as follows and enter the following remarks. Applicant acknowledges the Examiner's withdrawal of the previous restriction between species one through four.

In response to the present restriction requirement between Species I (polysilicon is oxidized under conditions that reduce redeposition of volatilized metal) and Species II (gate stack is etched under conditions that reduced redeposition of volatilized metal), Applicant elects Species I, without traverse. Applicant agrees with the Examiner's position that claims 9, 11, 14, 17, 18, 19, 21, and 22 are generic to both Species I and II. Applicant further believes that claims 10, 12, 15, and 20 are generic to both Species I and II.

In response to the present restriction requirement between Subspecies I (conditions comprise the presence of a gaseous F containing compound) and Subspecies II (conditions comprise the presence of a solid F containing compound), Applicant elects Subspecies I, without traverse. Applicant believes that claims 1, 2, 7, 9, 10, 11, 14, 17, 18, 19, 20, 21, and 22 are generic to both Subspecies I and Subspecies II.

Please enter the following amendment.